

**ABSTRACT**

A chemical amplification resist composition comprising a treated resin (1) obtained by contacting crude resin (1) with activated carbon, an acid generator and a

5 solvent,

wherein resin (1) is

(a) a (meth)acrylic resin which is insoluble or poorly soluble in an alkali aqueous solution and becomes soluble in an alkali aqueous solution by the action of an acid, and which comprises a repeating unit having an alicyclic hydrocarbon group in its side

10 chain or

(b) a styrenic resin which is insoluble or poorly soluble in an alkali aqueous solution and becomes soluble in an alkali aqueous solution by the action of an acid, and which comprises a repeating unit derived from hydroxystyrene, and a process for producing the same.

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